

Sozaraj Rasappa

List of Publications by Year in descending order

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Version: 2024-02-01

29
papers

628
citations

623734

14
h-index

580821

25
g-index

29
all docs

29
docs citations

29
times ranked

882
citing authors

#	ARTICLE	IF	CITATIONS
1	High molecular weight block copolymer lithography for nanofabrication of hard mask and photonic nanostructures. <i>Journal of Colloid and Interface Science</i> , 2019, 534, 420-429.	9.4	22
2	Morphology evolution of PS- b -PDMS block copolymer and its hierarchical directed self-assembly on block copolymer templates. <i>Microelectronic Engineering</i> , 2018, 192, 1-7.	2.4	12
3	Directed self-assembly of a high-chi block copolymer for the fabrication of optical nanoresonators. <i>Nanoscale</i> , 2018, 10, 18306-18314.	5.6	10
4	Nanopatterning via Self-Assembly of a Lamellar-Forming Polystyrene-block-Poly(dimethylsiloxane) Diblock Copolymer on Topographical Substrates Fabricated by Nanoimprint Lithography. <i>Nanomaterials</i> , 2018, 8, 32.	4.1	19
5	Nanoscale silicon substrate patterns from self-assembly of cylinder forming poly(styrene)- <i>i>block</i>-poly(dimethylsiloxane) block copolymer on silane functionalized surfaces. <i>Nanotechnology</i>, 2017, 28, 044001.</i>	2.6	4
6	Self-Assembled Nanofeatures in Complex Three-Dimensional Topographies via Nanoimprint and Block Copolymer Lithography Methods. <i>ACS Omega</i> , 2017, 2, 4417-4423.	3.5	5
7	High quality sub-10 nm graphene nanoribbons by on-chip PS-b-PDMS block copolymer lithography. <i>RSC Advances</i> , 2015, 5, 66711-66717.	3.6	22
8	A Highly Efficient Sensor Platform Using Simply Manufactured Nanodot Patterned Substrates. <i>Scientific Reports</i> , 2015, 5, 13270.	3.3	12
9	A facile route to synthesis of S-doped TiO ₂ nanoparticles for photocatalytic activity. <i>Journal of Molecular Catalysis A</i> , 2015, 406, 51-57.	4.8	96
10	Block Co-Polymers for Nanolithography: Rapid Microwave Annealing for Pattern Formation on Substrates. <i>Polymers</i> , 2015, 7, 592-609.	4.5	3
11	Soft Graphoepitaxy for Large Area Directed Self-Assembly of Polystyrene- <i>i>block</i>-Poly(dimethylsiloxane) Block Copolymer on Nanopatterned POSS Substrates Fabricated by Nanoimprint Lithography. <i>Advanced Functional Materials</i>, 2015, 25, 3425-3432.</i>	14.9	20
12	Graphoepitaxial Directed Self-Assembly of Polystyrene- <i>i>Block</i>-Polydimethylsiloxane Block Copolymer on Substrates Functionalized with Hexamethyldisilazane to Fabricate Nanoscale Silicon Patterns. <i>Advanced Materials Interfaces</i>, 2014, 1, 1300102.</i>	3.7	3
13	Study of the Kinetics and Mechanism of Rapid Self-Assembly in Block Copolymer Thin Films during Solvo-Microwave Annealing. <i>Langmuir</i> , 2014, 30, 10728-10739.	3.5	34
14	Fabrication of $3D$ Nanodimensioned Electric Double Layer Capacitor Structures Using Block Copolymer Templates. <i>Journal of Nanoscience and Nanotechnology</i> , 2014, 14, 5221-5227.	0.9	3
15	Rapid, Brushless Self-assembly of a PS-b-PDMS Block Copolymer for Nanolithography. <i>Colloids and Interface Science Communications</i> , 2014, 2, 1-5.	4.1	17
16	Swift Nanopattern Formation of PS- <i>b</i>-PMMA and PS-<i>b</i>-PDMS Block Copolymer Films Using a Microwave Assisted Technique. <i>ACS Nano</i>, 2013, 7, 6583-6596.</i></i>	14.6	67
17	Self-assembly of polystyrene-block-poly(4-vinylpyridine) block copolymer on molecularly functionalized silicon substrates: fabrication of inorganic nanostructured etchmask for lithographic use. <i>Journal of Materials Chemistry C</i> , 2013, 1, 7941.	5.5	34
18	Soft-graphoepitaxy using nanoimprinted polyhedral oligomeric silsesquioxane substrates for the directed self-assembly of PS-b-PDMS. <i>European Polymer Journal</i> , 2013, 49, 3512-3521.	5.4	12

#	ARTICLE	IF	CITATIONS
19	Fabrication of a sub-10 nm silicon nanowire based ethanol sensor using block copolymer lithography. Nanotechnology, 2013, 24, 065503.	2.6	30
20	Molecularly Functionalized Silicon Substrates for Orientation Control of the Microphase Separation of PS- <i>b</i> -PMMA and PS- <i>b</i> -PDMS Block Copolymer Systems. Langmuir, 2013, 29, 2809-2820.	3.5	30
21	Depth Profiling of PLGA Copolymer in a Novel Biomedical Bilayer Using Confocal Raman Spectroscopy. Langmuir, 2013, 29, 5905-5910.	3.5	4
22	Orientation and Alignment Control of Microphase-Separated PS- <i>b</i> -PDMS Substrate Patterns via Polymer Brush Chemistry. ACS Applied Materials & Interfaces, 2013, 5, 88-97.	8.0	36
23	The sensitivity of random polymer brush-lamellar polystyrene- <i>b</i> -polymethylmethacrylate block copolymer systems to process conditions. Journal of Colloid and Interface Science, 2013, 393, 192-202.	9.4	12
24	Tuning PDMS Brush Chemistry by UV ³ Exposure for PS- <i>b</i> -PDMS Microphase Separation and Directed Self-assembly. Langmuir, 2013, 29, 8959-8968.	3.5	13
25	Sub-15 nm Silicon Lines Fabrication via PS- <i>b</i> -PDMS Block Copolymer Lithography. Journal of Nanomaterials, 2013, 2013, 1-7.	2.7	4
26	Fabrication of Germanium Nanowire Arrays by Block Copolymer Lithography. Science of Advanced Materials, 2013, 5, 782-787.	0.7	3
27	Block Copolymer Self-assembly on Ethylene Glycol (EG) Self-assembled Monolayer (SAM) for Nanofabrication. Materials Research Society Symposia Proceedings, 2012, 1450, 1.	0.1	0
28	Block copolymer lithography: Feature size control and extension by an over-etch technique. Thin Solid Films, 2012, 522, 318-323.	1.8	21
29	Plasma etch technologies for the development of ultra-small feature size transistor devices. Journal Physics D: Applied Physics, 2011, 44, 174012.	2.8	80